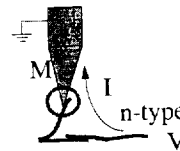


# Analysis of Carbon Nanotube-Semiconductor Diode Device

Toshishige Yamada  
NASA Ames Research Center

## Two experiments

Berkeley: metallic (M)-STM & semiconducting (S)-NT



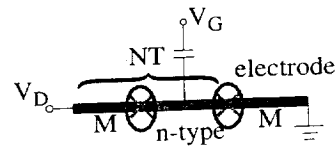
Science '97

I-V measurement

Two modes proposed: vacuum-gap & touching

NT shown to be n, not p

Delft: MS-NT & M-electrode with  $V_G$



Nature '99

gated  $I_D$ - $V_D$  measurement

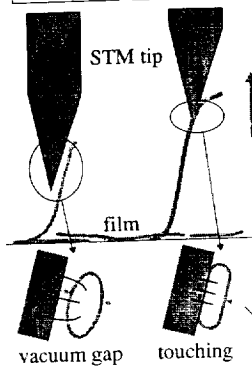
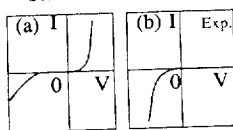
Gate modulation effects explained

Nature of MS and SM junctions clarified

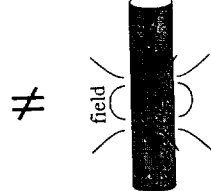
NT shown to be n, not p

## Tip (metal) - nanotube (semiconductor) contact experiment

Collins, Zettl, Bando, Thess, & Smalley,  
Science 278, 100 ('97)



1D cylindrical junction



Leonard & Tersoff,  
PRL 83, 5174 ('99)

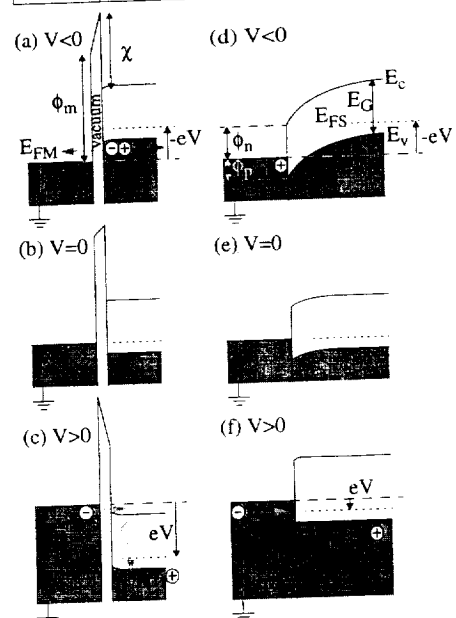
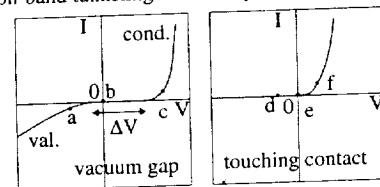
planar junction



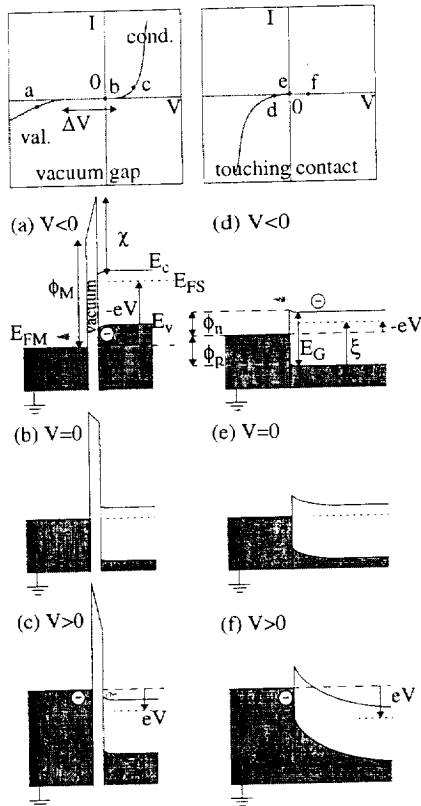
band alignment (BA) variable  
(against metal)  
T. Yamada, APL 78, 1739 ('01)

BA fixed  
(against H-Si)  
Hertel, Walkup, & Avouris,  
PRB 58, 13870 ('98)

p-type nanotube  
conduction-band tunneling = Schottky forward transport - contradictory



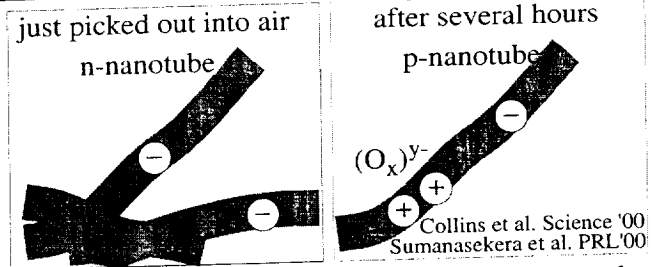
n-type nanotube  
valence-band tunneling = Schottky forward transport - consistent



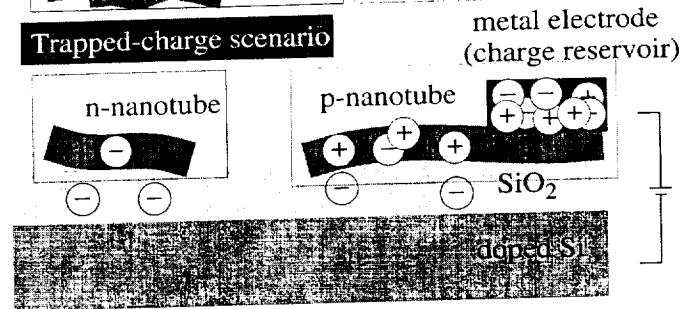
Why n-type, not common p-type?

n-type when produced due to unintentional dopants

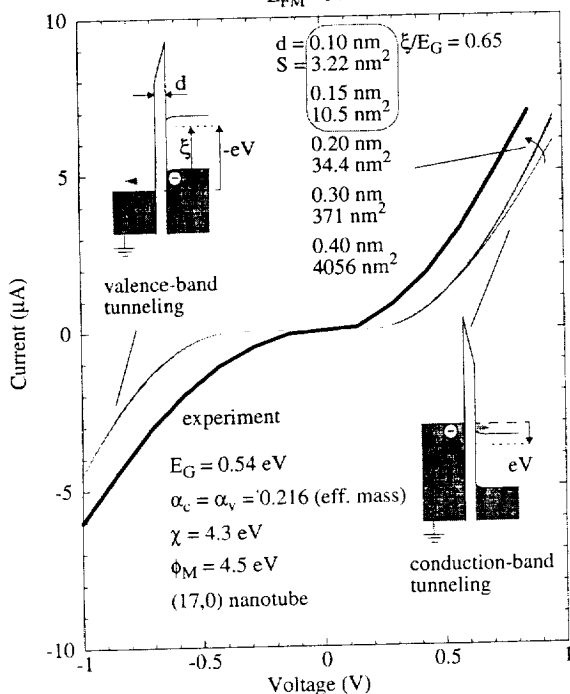
### Oxidation-in-air scenario



### Trapped-charge scenario

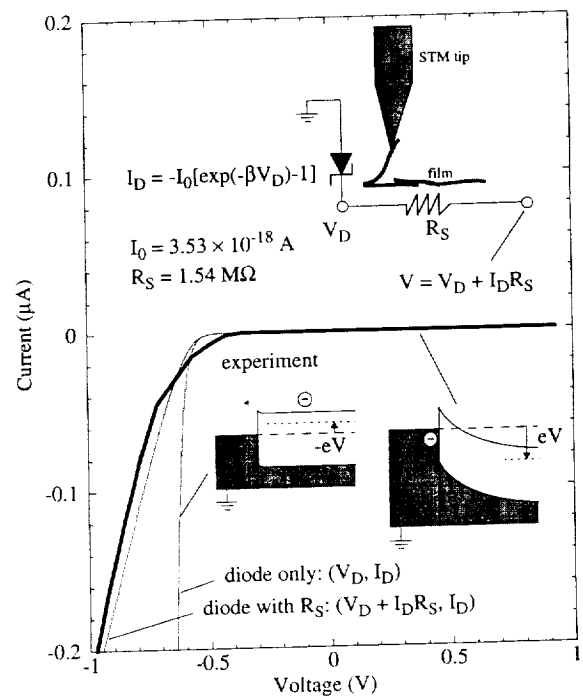


$$\text{tunneling } I_1 = \frac{4\pi m e S}{h^3} \int_{E_{FM} - eV}^{E_{FM}} dE \theta[\pm\{E - E_i(V)\}] \int_{-E(-1 \pm \alpha_i) \pm \alpha_i E_i(V)}^E dW D(W)$$

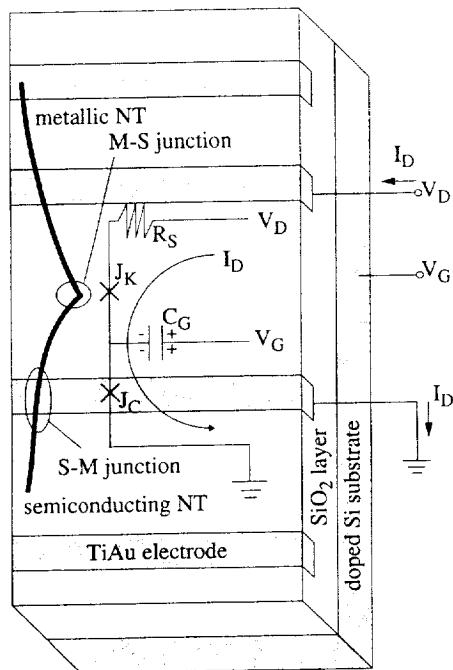


continuum approx. with 17 subbands, no band bending, parallel-momentum conserv. (wide tube limit),  $T = 0$ , WKB, no image potential

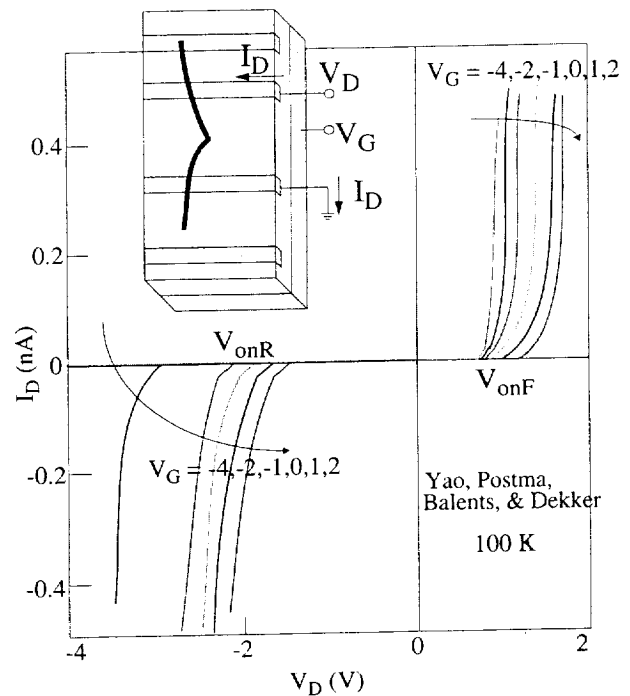
### Schottky formula



## Monolithic NT Schottky diode

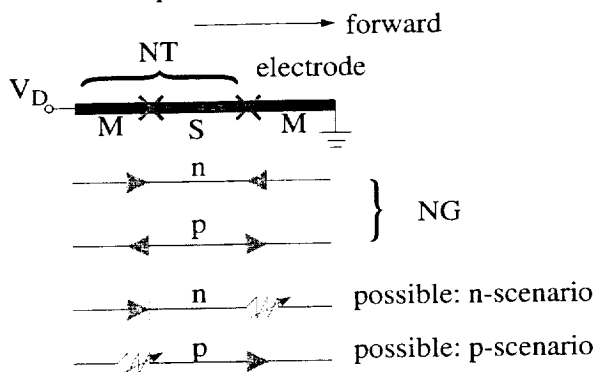


Yao, Postma, Balents, & Dekker, Nature **402**, 273 ('99)



For  $V_G \nearrow$ ,  $V_{onF} \nearrow$  and  $|V_{onR}| \searrow$

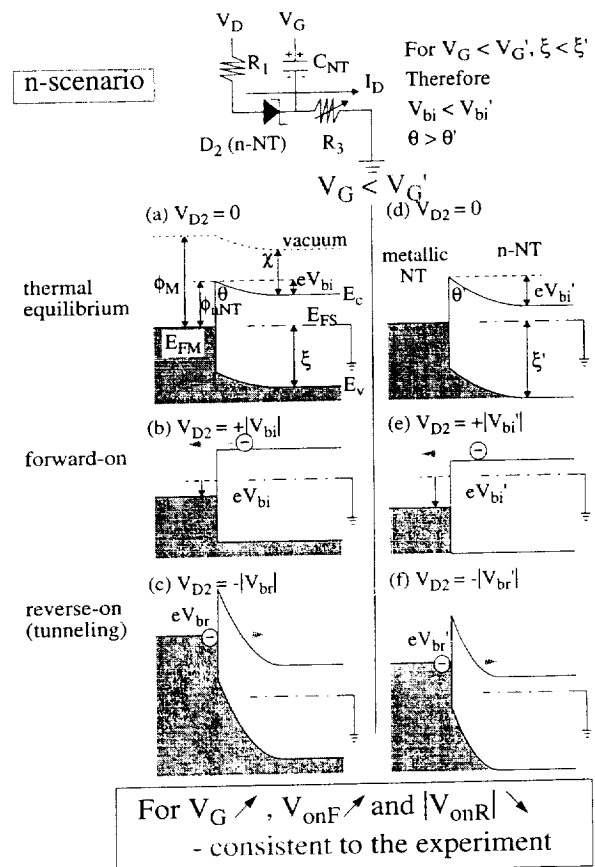
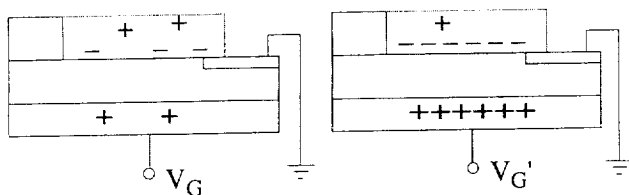
## Possible equivalent circuit with Schottky diodes



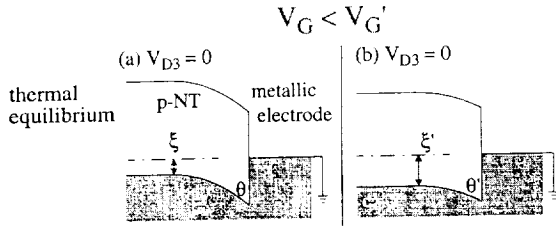
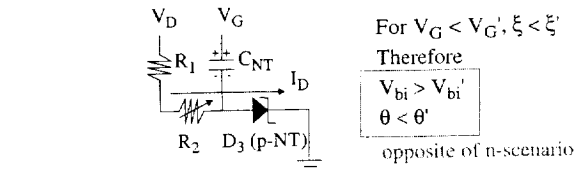
Increasing  $V_G$

$\Rightarrow$  increase  $\xi = E_F - E_v$ , regardless of p or n

$\Rightarrow$  not change the Schottky barrier



## p-scenario



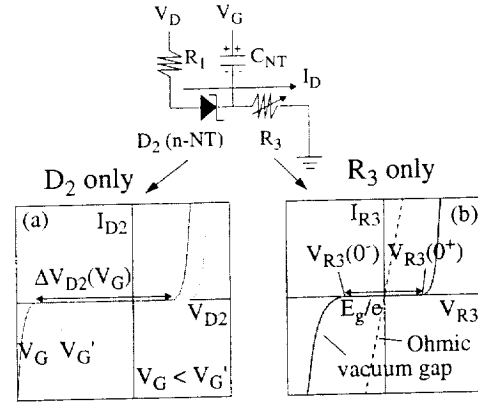
For  $V_G \nearrow$ ,  $V_{onF} \searrow$  and  $|V_{onR}| \nearrow$   
- contradictory to the experiment

Why n, not common p?

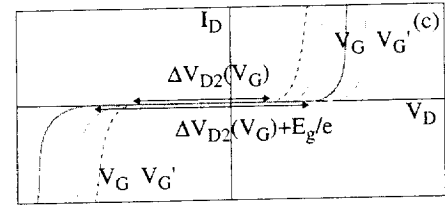
monolithic Schottky NT

low T ( $e^{-5000/100}/e^{-5000/300} \sim 3 \times 10^{-15}$ )

## Effect of contact to electrode at R3



$I_D - V_D$  for series of D2 and R3



With R3,  $\Delta V_{D2}$  is extended by  $E_g/e$

$V_{onF}$  and  $V_{onR}$  as a function of  $V_G$

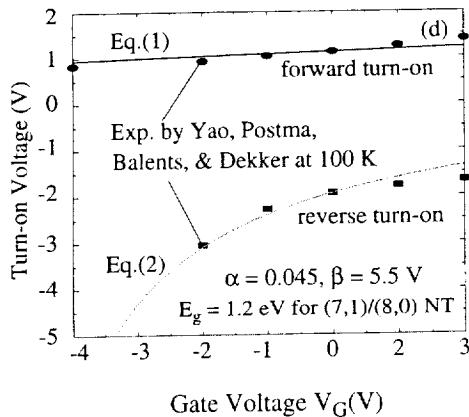
$V_{bi}$  modulated by  $V_G$  at the forward-on

$$V_{onF}(V_G) = V_{onF}(0) + \alpha V_G \quad (1)$$

the same  $\theta$  realized for different  $V_G$  at the reverse-on

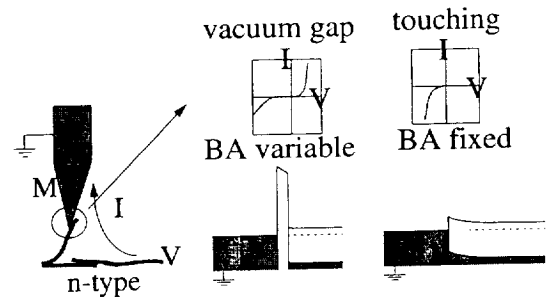
$$V_{onR}(V_G) = V_{onR}(0) + \alpha V_G + \frac{(V_{onF}(0) + |V_{onR}(0)| - E_g/e)V_G}{V_G + \beta} \quad (2)$$

where  $\alpha$  and  $\beta$  are parameters.

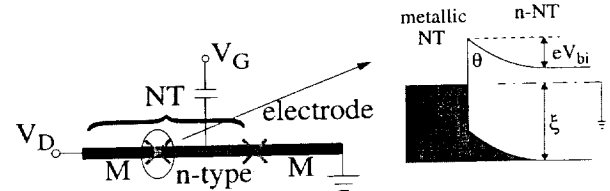


## Summary

- STM (M) - NT (S) junction modele



- Gated NT diode analysis



- Both are n-NT

STM - NT

Before air oxidation (p-doping)

gated kink NT diode at 100 K

monolithic kink NT

low T ( $e^{-5000/100}/e^{-5000/300} \sim 3 \times 10^{-15}$ )